Exam Question Solutions May 2012 Charge rentrality condition (a) n+Na = p+Nd des np = ni2 = pi2

$$P^{2} - (Na - Nd)P - Pi^{2} = 0$$

$$P = \frac{Na - Nd}{2} + \frac{Na - Nd}{2} \left[ 1 + \left( \frac{2Pi}{Na - Nd} \right)^{2} \right]^{1/2}$$

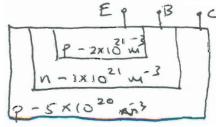
i) For P-type Na-Nd >> Pi  $n = \frac{p_{i}^{2}}{p} = \frac{p_{i}^{2}}{N_{0}-N_{0}} = \frac{p_{i}^{2}}{N_{0}} \left( = \frac{n_{i}^{2}}{N_{0}} \right)$  [2] Some people did it for n-type rather than p-type

ii) for compensation near intrinsic 
$$Pi \gg Ma-Nd$$

$$P = \frac{Na-Nd}{2} + \frac{Na-Nd}{2} \left[\frac{2Pi}{Na-Na}\right] = Pi$$

$$N = \frac{Pi^2}{P} = Pi \left(=n_i\right)$$

(10) Starting with Na = 5×10 00 1-e. P-type servicenductor lst diffusion has to be > 5 × 10 20 em3 but opposite deping type (n-type) 2nd differion has to be > 1st diffusion and p-type so from choices given 1st diffusion is 1×10° m with doubles and 2nd differious is 2x1021 m<sup>-3</sup> with acceptors [4:



N-1x10<sup>21</sup> m<sup>-3</sup>

This is a p-n-p transistor

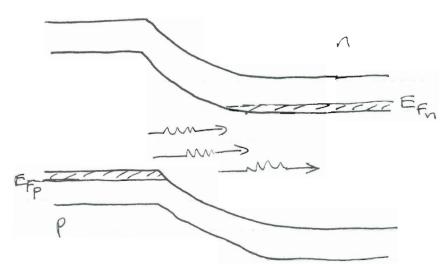
Many people tried to do a n-type base and got confused

In this semiconductor  $|Nd-Na| \ll ni (orpi)$ , so  $\begin{aligned}
&\text{P consector} &= 5 \times 10^2 \text{ m}^3 \\
&\text{N bose} &= 10^{21} - 5 \times 10^2 = 5 \times 10^2 \text{ m}^3 \\
&\text{P emitter} &= 2 \times 10^2 + 5 \times 10^2 - 1 \times 10^2 = 1.5 \times 10^2 \text{ m}^3 \\
&\text{Relatively few got this simple section fully correct minority carrier concentration are in the emitter is <math display="block">
&\text{N cond} &= (1.3 \times 10^6)^2 = 1.12 \times 10^8 \text{ m}^3
\end{aligned}$ 

(d) As the temperature increases, the ni value increases and the minority comies concentrations increases making the minority leakage currents in the transistor larger. At high temperatures, the semiconductor can appear to be intrinsic

You can increase the maximum operating temperature by increasing the doping levels in the transistor.

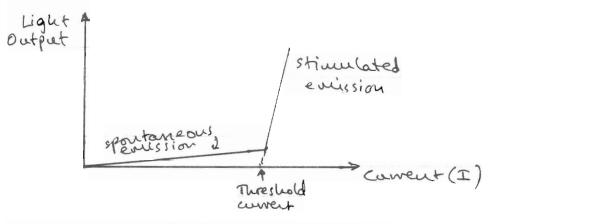
Most people got (d) correct



Heavily doped pour n doped regions und forward bias. Electron and holes diffuse across the depletion region and recombin hence photoms are eventted. Fermi levels more apart as shown

[6]

The difference between the Fermi levels is the voltage under forward bias and population inversion can occur and stimulated emission occurs. High reflectors are needed to form a cavity which reflects the photons and determines the exact basing wavelength.



Most people did well in part (a)

(b) maximum wavelength given by 1.24 = 0.688 pm minimum wavelength given by 1.24 = 0.5 th pm

In Gal is the QW material (nanower bound gap) and In All is the bornier material (wider bound gap).
No problems with (b) - some did not get the [4] QW material correctly identified.

This is an increase in energy over InGal of 1.907= 1.8=107 meV.

1 = 107 meV

= h2 (me\* + mix) 8mox107x103x1.6x10-19

 $= 3.518 \times 10 \times 12.54 = 4.412 \times 10^{-17}$ 

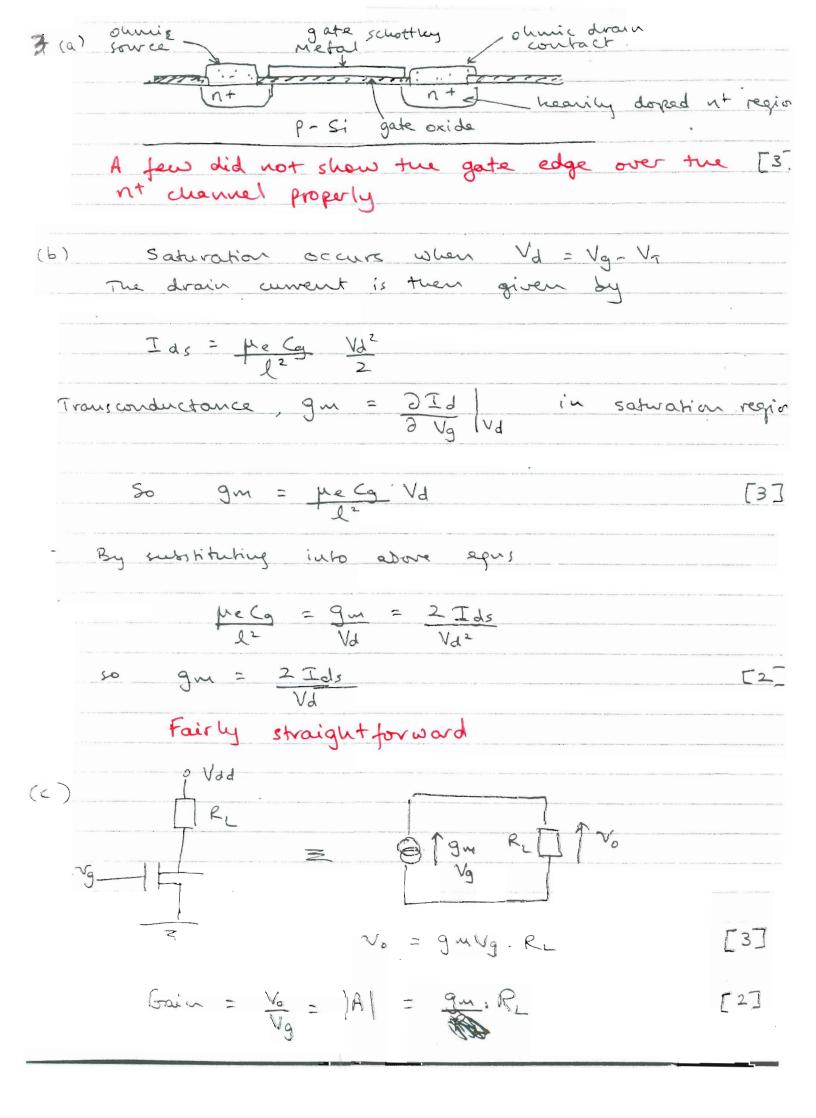
Many people got this correct - some forgot

Many people got this correct - some forgot the e so had a huge error

There is an uncertainty of ±0.5 nm. This affects the 1st bound level energy as:

DE & 1 (L ±0.5mm)2

the accuracy of the emitted wavelength would therefore be higher in structure with a large L as the effect of the ±0.5 mm would be relatively small. The opposite is true in smaller L structures and the ±0.5 mm would result in a poorer accuracy. Several people [3] calculated this - a description would have sufficed. At short wavelengths, when L becomes small, the height of the barrier material and tunnerlying will affect the shortest wavelength that can be achieved. Quite a few got (d) incorrect despite mentioning [2] tunnelling.



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3 cout. .. 30 = gm RL = 2 Ids. RL = 2 Ids. RL = 2 Ids. RL = Vd (Vdd-Ill)
           30 = 2.30 \times 10^{-3} R_L
100 - 30 \times 10^{-3} R_L
           gives R = 3.125 KS
 Very few got this completely correct_ seemed to confuse Vd and 1000 supply.
           Vd = 100 - 30×103. 3.125 KR
            9m = \frac{2. \text{ Tds}}{\text{Vd}} = \frac{2 \times 30 \times 10^{-3}}{6.25} = 9.6 \text{m/s}
   Since gur also = pre Cg Vd
               L^2 = \mu e C_9 Vd = 0.13 \times 10^{-12} \times 6.25
                 l = 9.2 pm (gate length)
          Cg = Eo Er Area = Eo Er l, widter
     length = 0.1 width => width = 92 pm
         to = Eo Er l. widte = 11.8 × 8.85×10.2 × 9.2 pm × 92
           to = 88 nm
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Very few managed to do this correctly

[5]

(a) 
$$E = \frac{1}{2} m V^2 = \frac{p^2}{2m}$$
 (as momentum  $p = mv$ )

Differentiating this twice gives:
$$\frac{dE}{d\rho} = \frac{1}{m}, \quad \frac{d^2E}{d\rho^2} = \frac{1}{m}$$

In a semiconductor, replace on with an 'effective' mass, m' to account for lattice interactions

[4]

$$m^* = \left(\frac{d^2E}{d\rho^2}\right)^{-1}$$

Most managed this with few problems.

(b) 
$$E-K$$
 relationship is assumed parabolic, so:  
 $E=A+BK^2$ , where A, B are constants

Bandgap at K=0 for direct band-gap semiconductor, so A=1.8eV

$$\frac{dE}{dk} = 0 + 2BK$$
,  $\frac{d^2E}{dk^2} = 2B$ ,  $\frac{d^2E}{dp^2} = 2B$  (  $p = \frac{1}{2}$ )

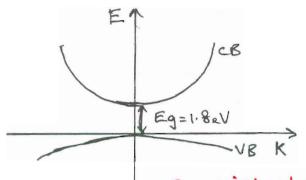
$$\frac{1}{2B} = \frac{h^2}{2B} = 0.09 \times 9.11 \times 10^{33}$$

$$B = \left(\frac{6.626 \times 10^{34}}{2 \text{ T}}\right)^{2} \times 1 \times \frac{1}{0.09 \times 9.11 \times 10^{31}} = 0.68 \times 10^{-37} \text{ Jm}$$

$$= 4.25 \times 10^{-19} \text{ eV}$$

Most got this approximately correct - some did not give units or mixed eV and In together

4 b.



The &x higher mass for holes results in a nuch 'flatter' VB structure

Surprisingly many got this wrong - did not seem to know how m\* changed with E-K

In reality, the electron effective mass increases as you approach the Brillouin zone edge. The CB energy does not continue to increase at the same rate as you more away from K=0 and eventually becomes constant (electron relocity = 0) Relatively few got how m\* changes correct - several gave the opposite answer

C Heisenberg Uncertainty Principle ∆PAX ≥ t1/2

This implies that both parameters of a particle, i.e. the momentum and position, cannot be measured simultaneously to an arbitrary high degree of precision.

confusing h, th etc.

d. de Broglie:  $p = mv = \frac{h}{\lambda}$  where h = Plank's const

 $\lambda = \frac{h}{mv}$  this was apparently easy

The P.E. of electron = K.E.

\[ \frac{1}{2} mv^2 = eV \]

$$7 = \left(\frac{2eV}{m}\right)^{1/2}$$

$$80 \lambda = \frac{h}{(2eVm)^{1/2}} = \frac{1.225 \text{ nm}}{V^{1/2}}$$

when V = 50 V ,  $\lambda = 0.17$  nm so this is the minimum feature size

Relatively few got the correct numerical answer - despite this being a tutorial type question